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## **Table of Contents**

AN EFFECTIVE METHOD OF CONTOUR EXTRACTION FOR SEM IMAGE BASED ON DCNN Tao Zhou, Xuelong Shi, Yan Yan, Chen Li, Shoumian Chen, Yuhang Zhao, Wenzhan Zhou, Kan Zhou, Xuan Zeng	1
PATTERN ROUGHNESS ANALYSES IN ADVANCED LITHOGRAPHY: POWER SPECTRAL DENSITY AND AUTOCORRELATION Yuyang Bian, Xijun Guan, Biqiu Liu, Xiaobo Guo, Cong Zhang, Jun Huang, Yu Zhang	5
FAST AND ACCURATE MACHINE LEARNING INVERSE LITHOGRAPHY USING PHYSICS BASED FEATURE MAPS AND SPECIALLY DESIGNED DCNN Xuelong Shi, Yan Yan, Tao Zhou, Xueru Yu, Chen Li, Shoumian Chen, Yuhang Zhao	9
3M IMMOBILIZED MICRO-BED ION EXCHANGE RESIN BED TECHNOLOGY TREATMENT OF PGMEA Majid Entezarian, Bob Gieger, Garry Wang	12
EVALUATING THE PROCESS PERFORMANCES OF BINARY, PSM AND OMOG MASKS IN ADVANCED TECHNOLOGY NODE Weimei Xie, Yanpeng Chen, Shirui Yu, Yu Zhang	16
NOVEL TARGET DESIGN FOR THICK RESIST LAYERS OVERLAY MEASUREMENT IMPROVEMENT Chao Fang, Jinyu Qiu, Pandeng Xuan, Yaobin Feng, Lingyi Guo, Jiahui He, Gang Xu, Jin Zhu, Jincheng Pei	19
REAL TIME PROCESS MONITORING USING DIFFRACTION-BASED OVERLAY MEASUREMENTS FROM YIELDSTAR Henry Chen, Jimmy Chang, Sheng-Tsung Tsao, Junjun Zhang, Jie Du, Congcong Fan, Alex Huang, David Xu, Sam Liu, Liang Wu, Kimi Yang, Ning Gu, Liping Ren, Jian Wu, Alexander Tan II, Sunny Xia, Ivan Mao	23
MACHINE LEARNING VIRTUAL SEM METROLOGY Yan Yan, Xuelong Shi, Tao Zhou, Bowen Xu, Chen Li, Yifei Lu, Ying Gao	27
MASK OPTIMIZATION BASED ON ARTIFICIAL DESIRED PATTERN Fei Peng, Chengqun Gui, Yi Song, Yijiang Shen	31
A NOVEL SEM IMAGE BASED ADVANCED LITHOGRAPHY PROCESS CONTROL PROVIDING QUICK FEEDBACK Xuedong Fan, Lijun Chen, Jun Zhu, Haichang Zheng, Xiaolong Wang, Yancong Ge, Yu Zhang, Abhishek Vikram, Guojie Cheng, Hui Wang, Qing Zhang, Wenkui Liao	35
ULTRAFAST AND ACCURATE PROXIMITY EFFECT CORRECTION OF LARGE-SCALEELECTRON BEAM LITHOGRAPHY BASED ON FMM AND	39

SAAS	
Chengyang Hou, Wenze Yao, Wei Liu, Yiqin Chen,Huigao Duan, Jie Liu	
PRELIMINARY ROUND OF OPC DEVELOPMENT IN 180NM NODE SILICON PHOTONICS MPW PLATFORM	42
Zengzhi Huang, Shijie Chen, Weiran Huang, Zhenguo Zheng, Guowei Cao, Junbo Feng	
FAST MASK NEAR-FIELD CALCULATION USING FULLY CONVOLUTION NETWORK	45
Jiaxin Lin, Lisong Dong, Xu Ma, Taian Fan, Rui Chen, Yayi Wei	
OVERLAY MARK SUB STRUCTURE DESIGN TO IMPROVE THE CONTRAST Libin Zhang, Cong Lu, Yaobin Feng, Yayi Wei, Xiaojing Su, Le Ma, Lisong Dong	49
PHOTORESIST FOR EXTREME ULTRAVIOLET LITHOGRAPHY Peipei Tao, Li Sheng, Qianqian Wang, Hao Cui, Xiaolin Wang, Xiangming He, HongXu	53
OPO MEASUREMENT IMPROVEMENT IN ADVANCED DRAM WITH TUNABLE WAVELENGTH IMAGING	57
Yunsheng Xia, Rui Qin, Andy Lan, Joer Huang, Congcong Fan, Shaowen Qiu, Dong Xue, Joshua Tao, Kun Gao, Haoran Li, Susie Lu, Hongpeng Su, Linfei Gao, Jinyan Song	
SOURCE OPTIMIZATION UNDER THICK MASK MODEL Yang Liu, Yanqiu Li, Lihui Liu, Yiyu Sun, Pengzhi Wei, Enze Li	63
DEVICE-CIRCUIT CO-OPTIMIZATION FOR NEGATIVE CAPACITANCE FINFETS BASED ON SPICE MODEL	67
Jiali Huo, Weixing Huang, Fan Zhang, Qiang Huo, Weizhuo Gan, Haoqing Xu, Huilong Zhu, Yongliang Li, Zhenhua Wu, Huaxiang Yin	
MODIFIED ANTI-WINDUP CONTROL FOR HIGH PRECISION MOTION SYSTEM	71
Zhipeng Wu, Jing Li, Dongdong Xie, Minxia Ding	
MACHINE LEARNING HOTSPOT PREDICTION SIGNIFICANTLY IMPROVE CAPTURE RATE ON WAFER	75
Wei Yuan, Yifei Lu, Ming Li, Bingyang Pan, Ying Gao, Yu Tian, Zhi-qin Li, Liang Ji, Ying Huang, Hao Chen, Yueliang Yao, Sean Park	
INVESTIGATION OF A NEW METHOD TO WEIGH THE DATA USED FOR OPC MODEL CALIBRATION	79
Le Ma, Libin Zhang, Liwan Yue, Zhibiao Mao, Yayi Wei	
AN APPLICATION OF CHEBYSHEV SPECTRAL METHOD INMODELING THE DIFFUSION OF THE ACID DURING PEBPROCESS Pengjie Kong, Lisong Dong, Yayi Wei	82
THE IMPACT OF LENSES ABERRATION ON CD AND POSITION FOR LOW K1 LITHOGRAPHY	85

#### REDUCING SYSTEMATIC DEFECTS USING CALIBRE WAFER DEFECT ENGINEERING AND MACHINE LEARNING SOLUTIONS

Qian Xie, Liang Cao, Qijian Wan, Xinyi Hu, Chunshan Du, David Wang, Jet Jiang, Frank Hou, Gavin Li, Summy Chen, Marfei Fei, Elven Huang, Sankaranarayanan Paninjath, Saikiran Madhusudhan, Leo Tian

ALTERNATIVE TIP- AND LASER- BASED NANOFABRICATION UP TO 100 MM ON FLAT AND NON-FLAT SURFACES WITH SUBNANOMETRE PRECISION Eberhard Manske 92